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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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R. Stokes

Priority Application Serial No. .... 09/332,271  
Priority Filing Date ..... June 11, 1999  
Inventor ..... Klaus Florian Schuegraf et al.  
Assignee ..... Micron Technology, Inc.  
Priority Group Art Unit ..... 2815  
Priority Examiner ..... E. Lee  
Attorney's Docket No. .... MI22-1741  
Title: Methods for Forming Wordlines, Transistor Gates, and Conductive Interconnects,  
and Wordline, Transistor Gate, and Conductive Interconnect Structures

**PRELIMINARY AMENDMENT**

To: Assistant Commissioner for Patents  
Washington, D.C. 20231

From: D. Brent Kenady (Tel. 509-624-4276; Fax 509-838-3424)  
Wells, St. John, Roberts, Gregory & Matkin P.S.  
601 W. First Avenue, Suite 1300  
Spokane, WA 99201-3828

**AMENDMENTS**

**In the Specification**

At page 1, before the "Technical Field" section, insert the following paragraph in accordance with 37 C.F.R. § 1.121(b)(1)(ii):

**~RELATED PATENT DATA**

This patent resulted from a divisional application of U.S. Patent Application  
Serial No. 09/332,271, filed June 11, 1999.~.